

ABSTRACT

Disclosed is a near-field exposure
5 method and apparatus, a near-field exposure mask,
and a device manufacturing method, wherein
exposure is carried out on the basis of near field
light. Specifically, the near-field exposure
method disclosed is arranged so that a pressure
10 difference is applied to between a front face and
a rear face of an elastically deformable exposure
mask to cause deformation of the exposure mask in
accordance with a substrate to be exposed and to
cause the exposure mask surface to follow a
15 surface irregularity state of the substrate such
that these surfaces are closely contacted to each
other, for exposure based on near field light.
The pressure difference applied to between the
front and rear faces of the exposure mask is set
20 at a predetermined pressure difference
corresponding to surface roughness of the
substrate to be exposed.